

Introduction on My Current Research Interest

Albert Shihchun Lin, National Chiao-Tung
University, Hsinchu, Taiwan

Biography

<http://albertlin.weebly.com/>

林詩淳(Albert Lin, Associate Professor, National Chiao Tung Univ.)

Associate Professor, National Chiao-Tung University

Room 503, Engineering Building IV, No.1001 University Road, Hsinchu, Taiwan
新竹市大學路1001號交通大學工程四館503室

Lab: +886 35712121 ext54242 (room ED314)
Office: +886 35712121 ext54267 (room ED503)
Phone: 0921 755140(手機)
Email: htd5746@gmail.com

Website: <http://albertlin.weebly.com>



個人網頁:

<http://albertlin.weebly.com>

實驗室網頁或詳細履歷:

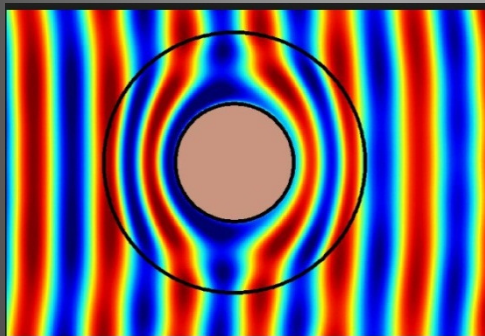
學經歷

- EE, University of Michigan, Ann Arbor, PhD 2010
- EE, University of Michigan, Ann Arbor, MS 2007
- EE, National Chiao-Tung University, Taiwan, BS 2005

Current Research Interest

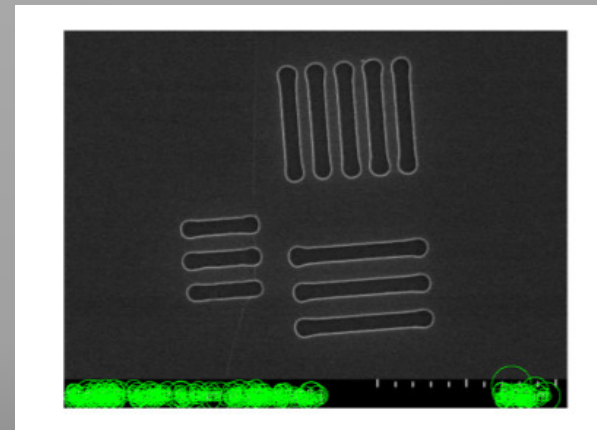
[10.1109/JPHOT.2019.2938536](https://doi.org/10.1109/JPHOT.2019.2938536)

Silicon Nano-photonics

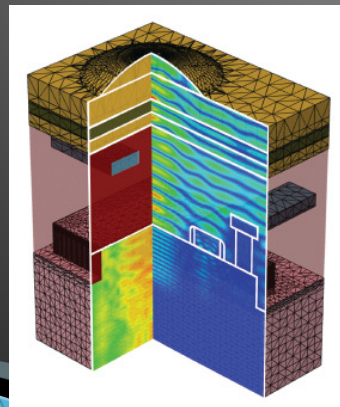


Device Simulation

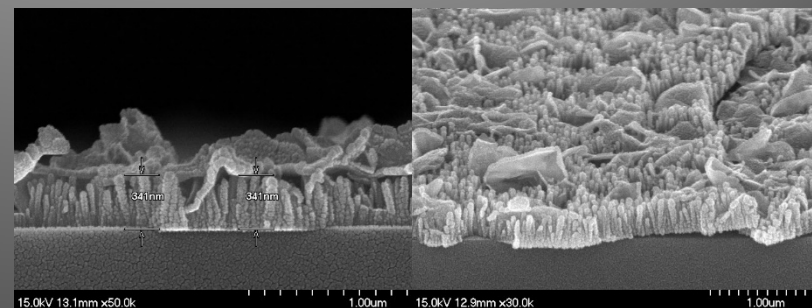
Intelligent semiconductor manufacturing



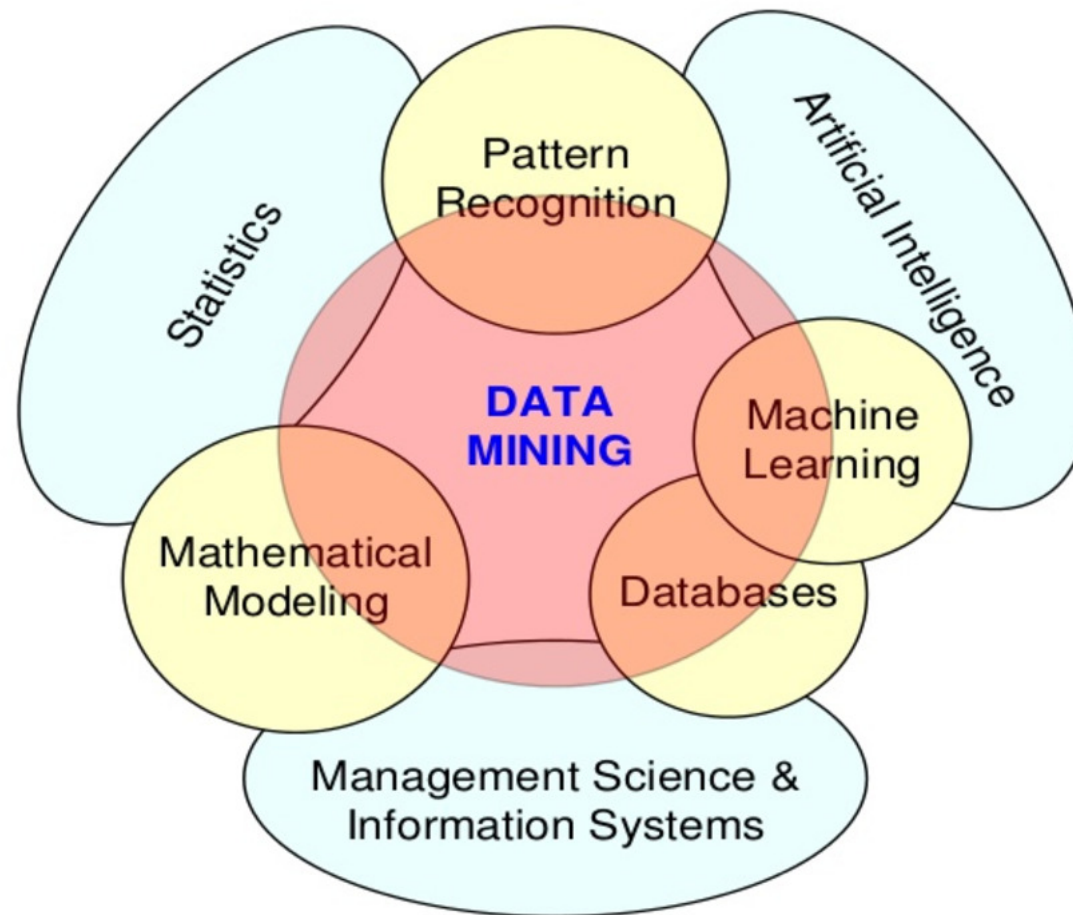
Device Process



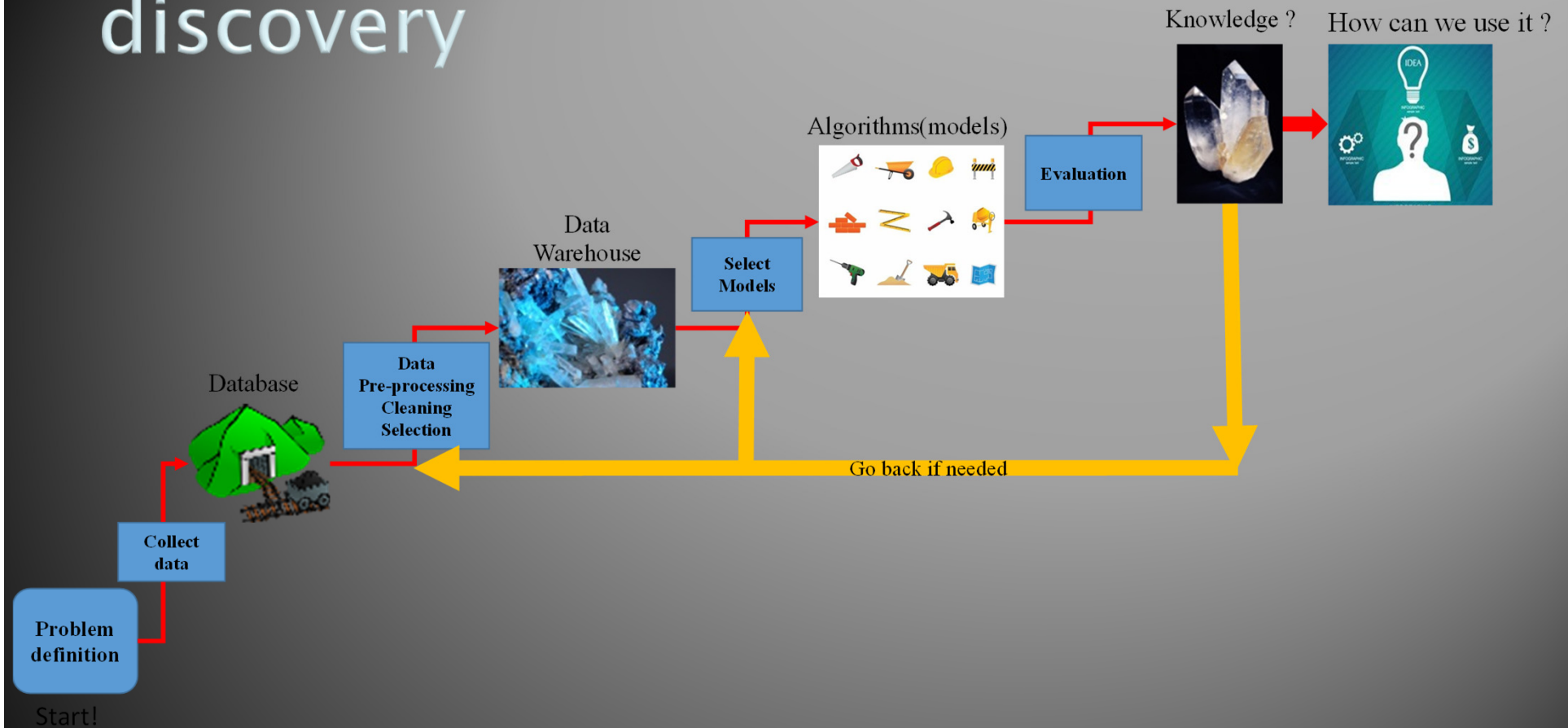
Ref: Sentaurus Device Manual



Relations between Data Mining & Machine Learning



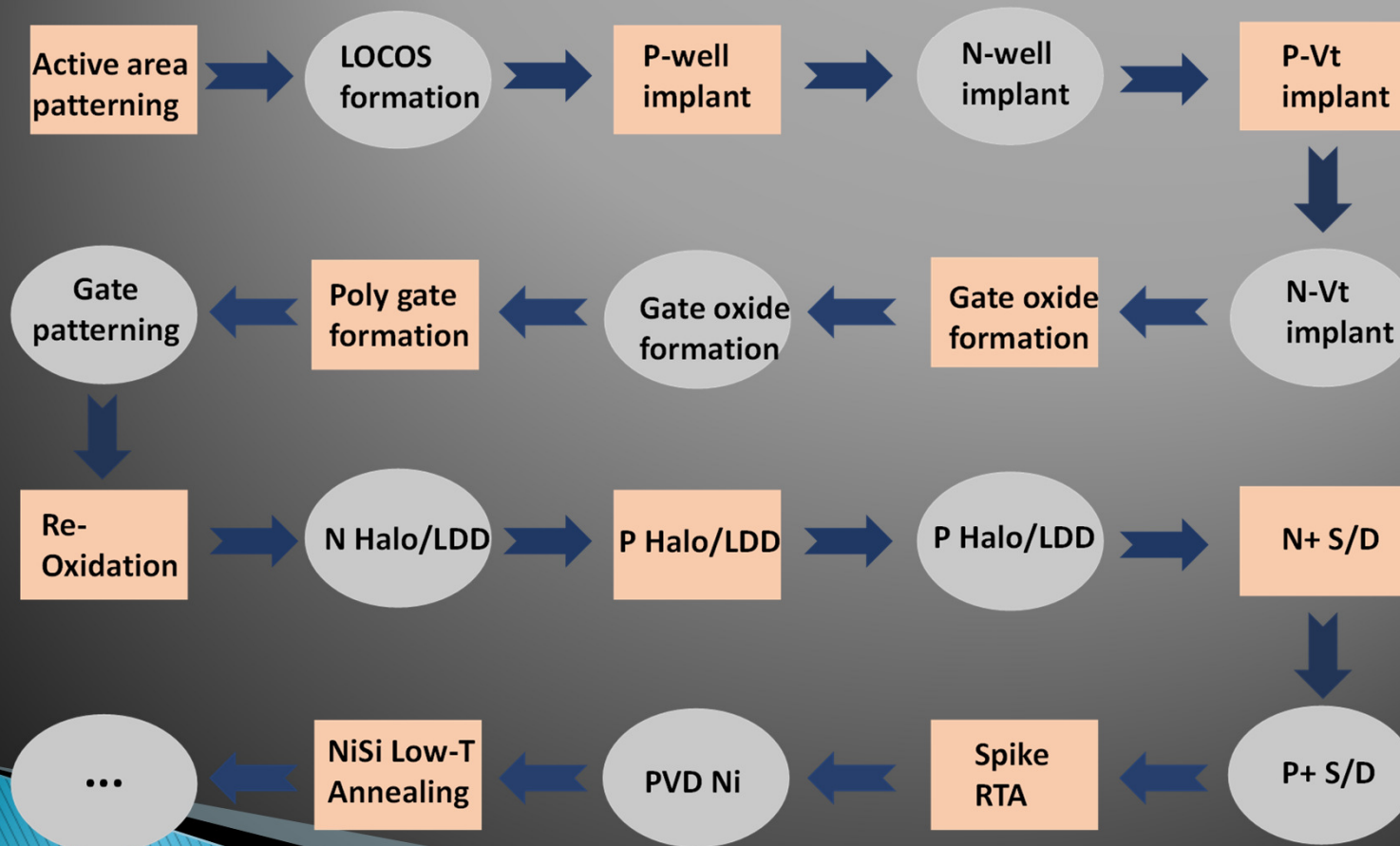
Data Mining: Process of knowledge discovery



Data mining steps

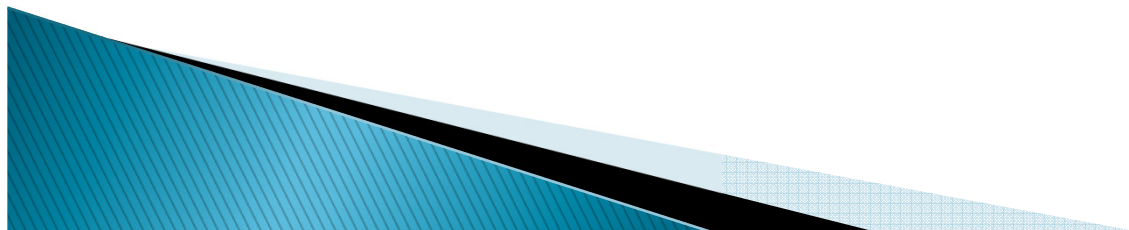
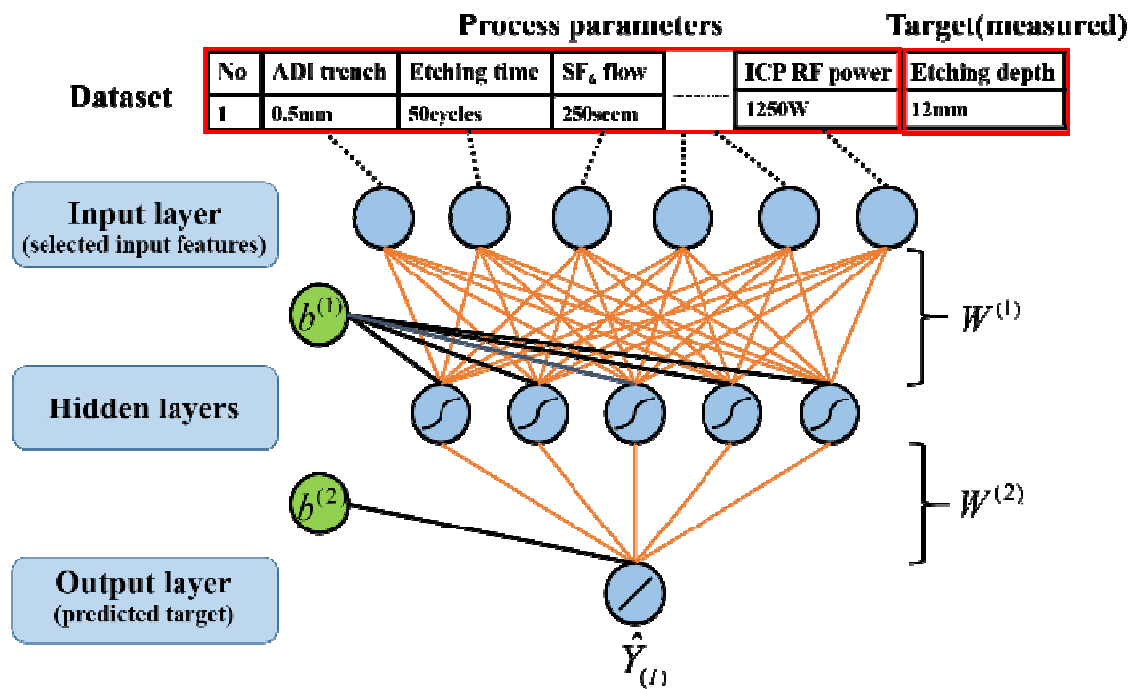
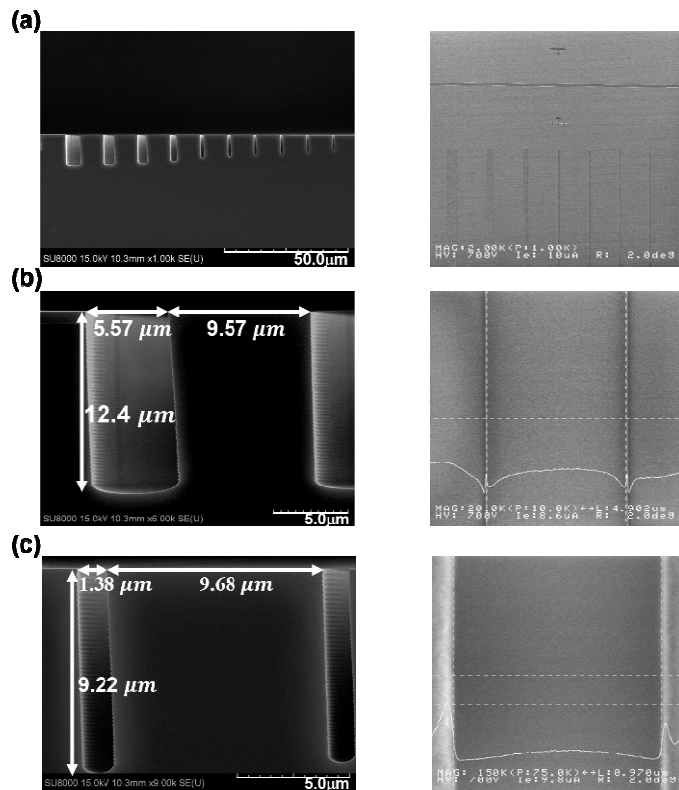
Data Mining in Semiconductor Processing

The Standard 90nm CMOS process require 150 steps and there are 1000+ parameters used during the whole process.



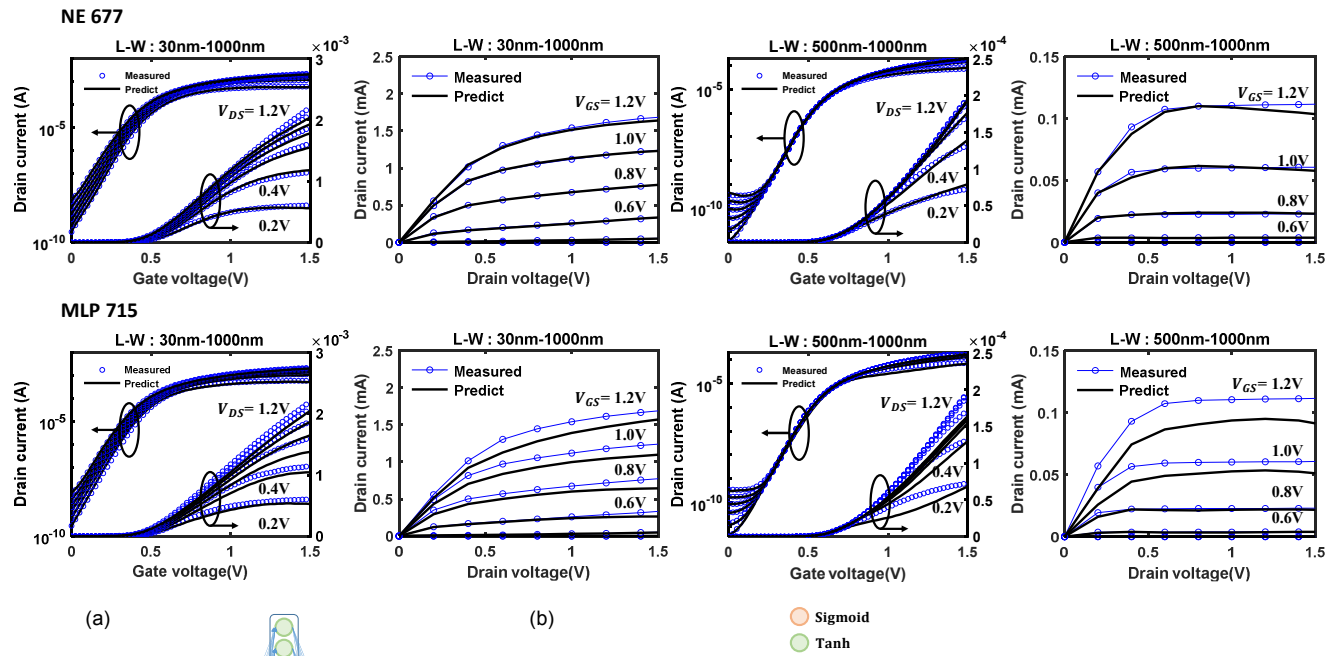
Data Mining in Semiconductor Processing

IEEE Access 7, 130168-130179



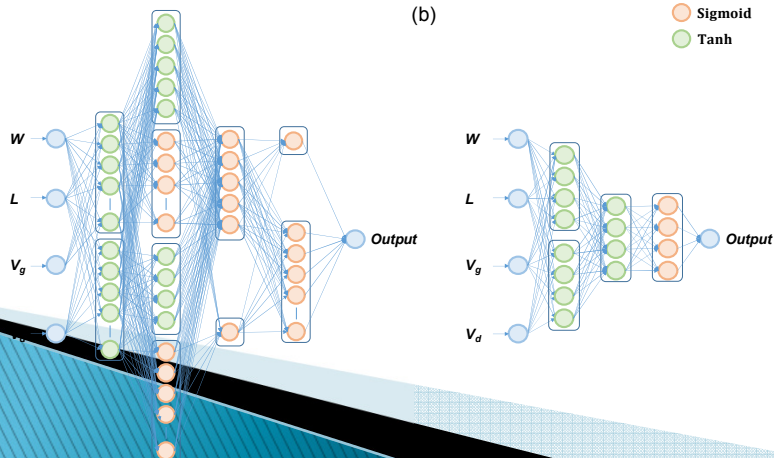
Data Mining in Semiconductor Processing

IEEE Access 9, 159048-159058



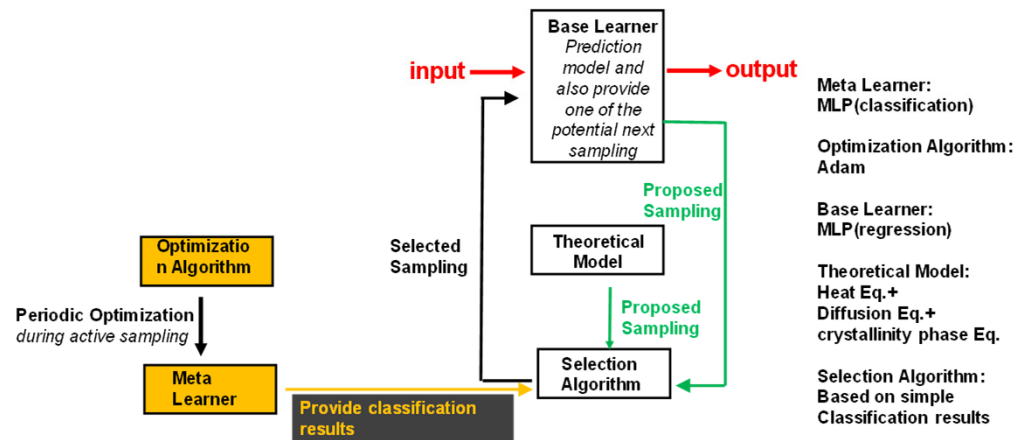
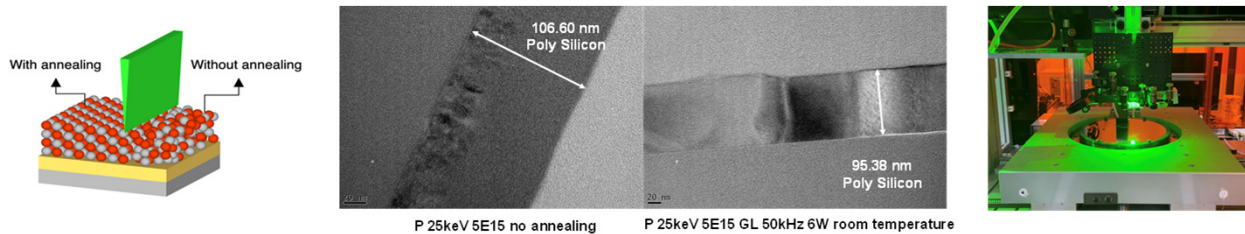
(a)

(b)



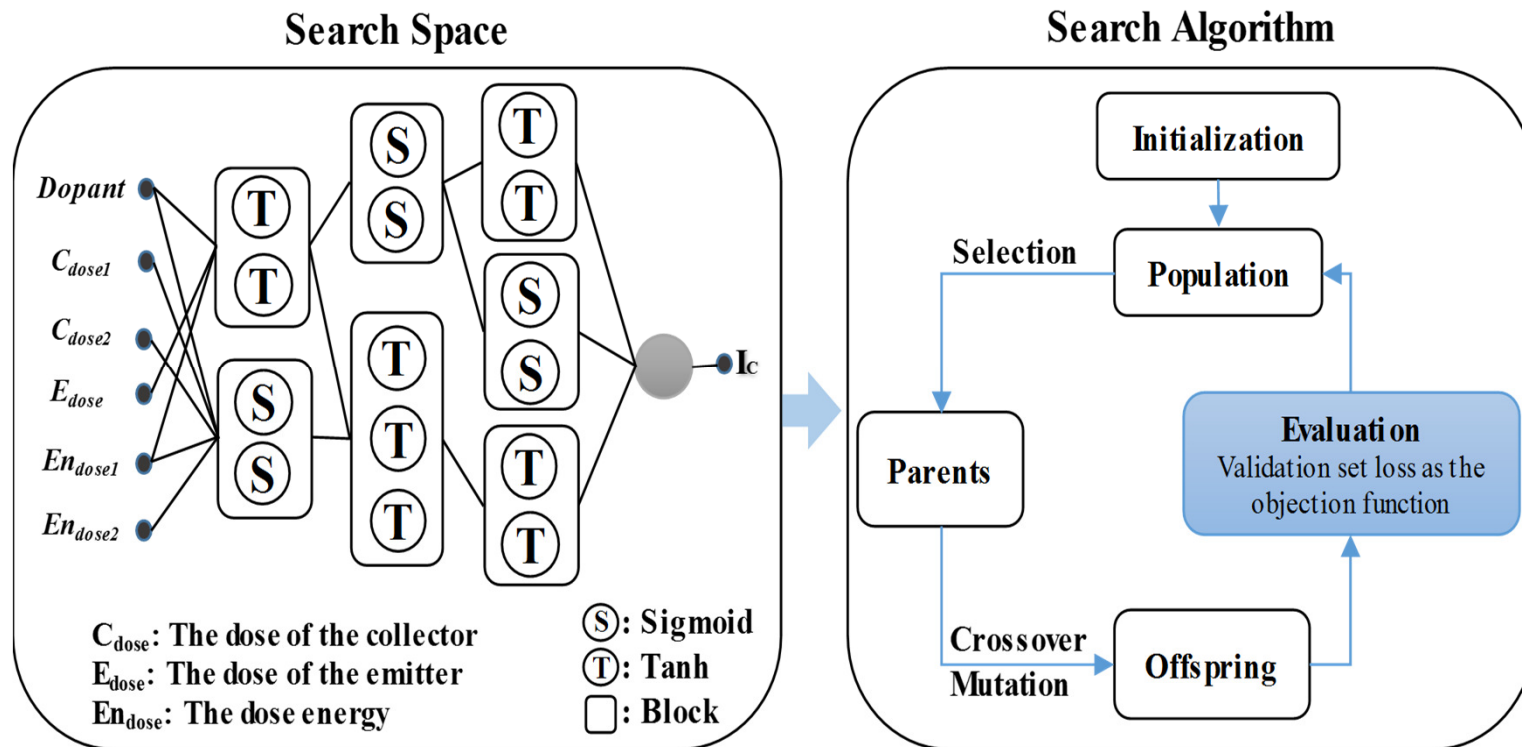
Data Mining in Semiconductor Processing

ACS omega 8 (1), 737-746



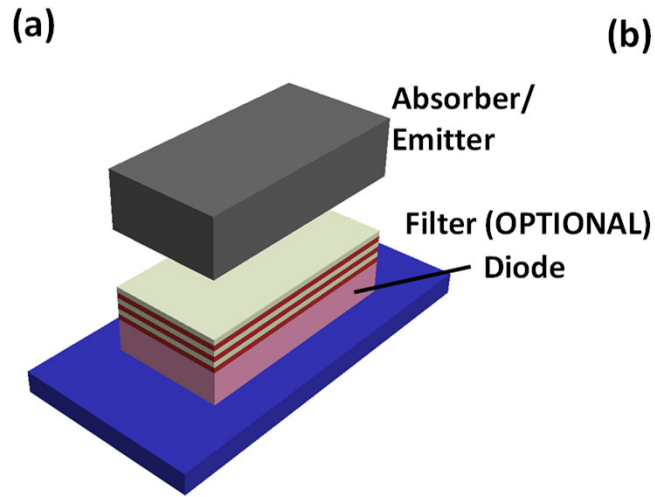
Data Mining in Semiconductor Processing

ACS omega 8 (31), 28877-28885

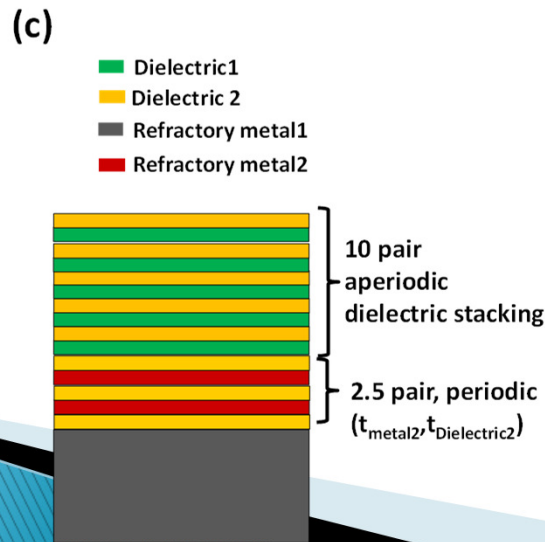
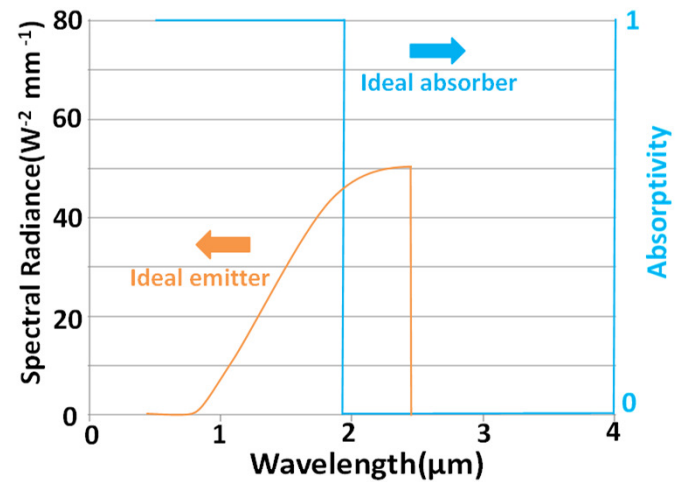


Silicon Photonics

Thermo-photonics in silicon platform

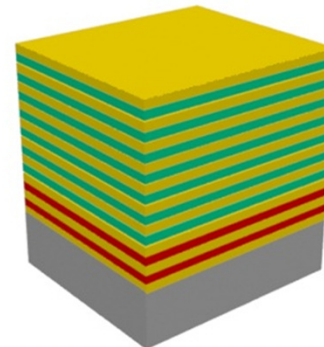


(b) IEEE Photonics Journal 8 (4), 1-9



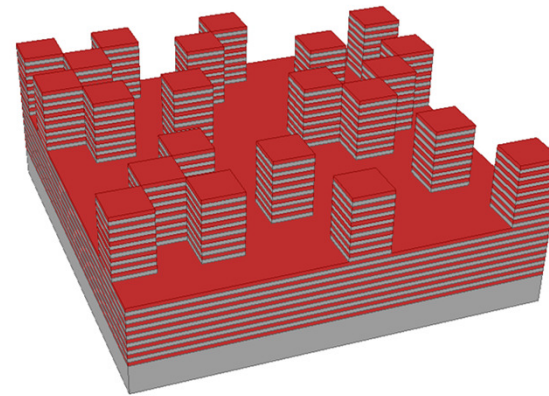
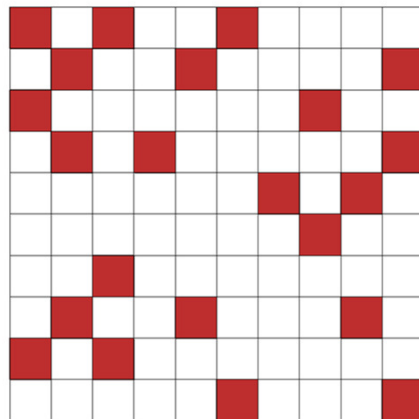
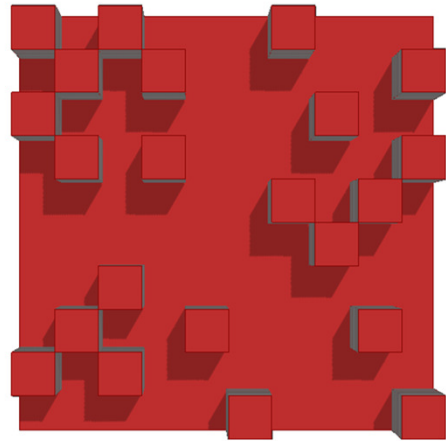
(d)

- Dielectric1: AlN, Al₂O₃, SiO₂, Si₃N₄, TiO₂, Si
- Dielectric 2: AlN, Al₂O₃, SiO₂, Si₃N₄, TiO₂, Si
- Refractory metal1: Ta, W
- Refractory metal2: Ta, W, Ti, Rh, Ru, Mo



Silicon Photonics

Metamaterials in Silicon processing

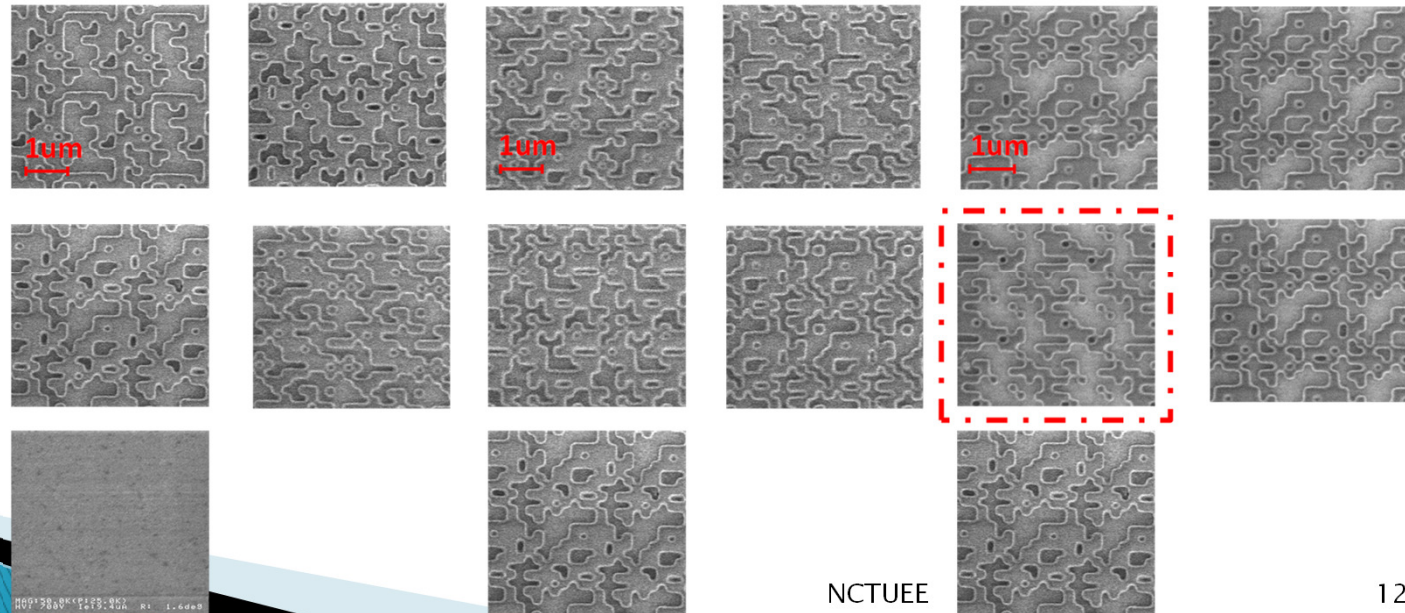


1st generation

2nd generation

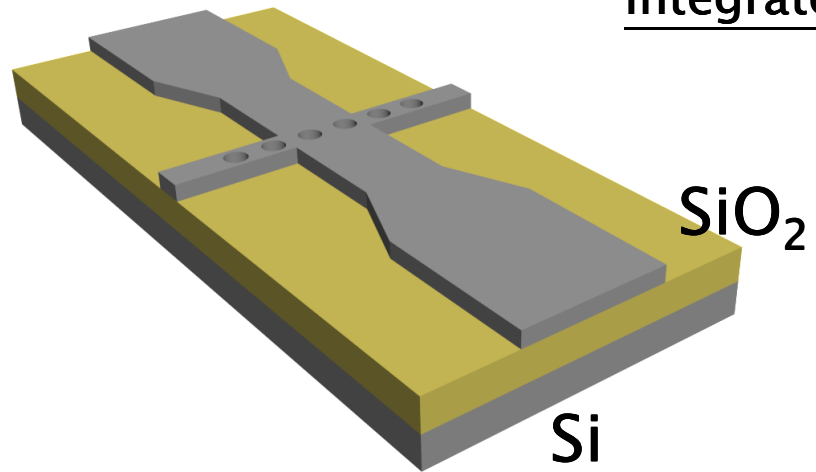
3rd generation

Optics Express
23 (19), A1324-
A1333

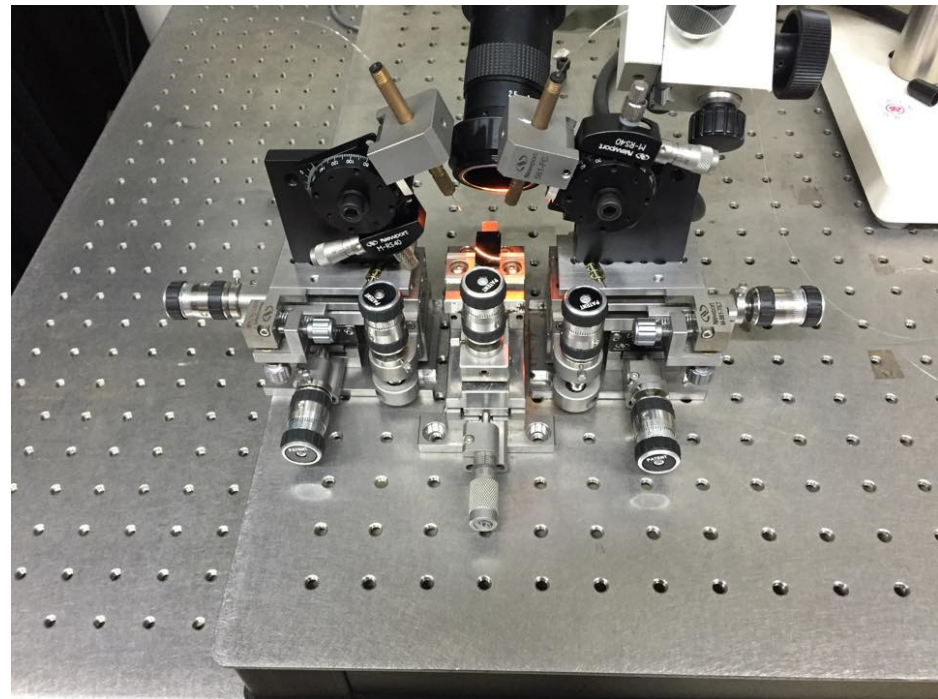
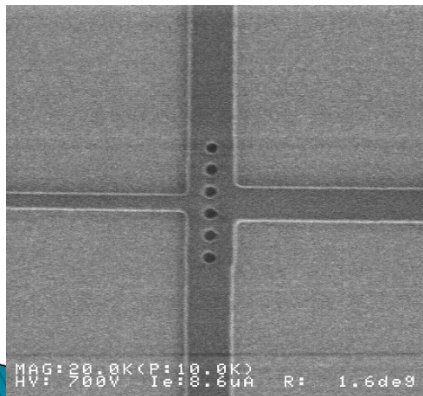


Silicon Photonics

Integrated Silicon Photonics



3D structure figure



Description to Drift-Diffusion Model for IBSC

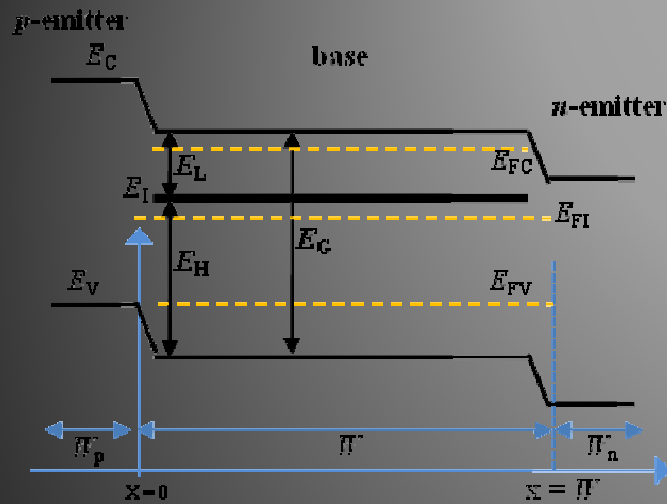


Illustration of the prototype intermediate band solar cell device structure and energy band diagram.

Effect of charge in intermediate band

$$\vec{\nabla} \cdot \epsilon_r \epsilon_0 \vec{\nabla} \psi = q (N_A^- - N_D^+ + n - p - fN_I)$$

$$\vec{\nabla} \cdot \vec{J}_n = q (G_{VC} + G_{IC} - R_{CV} - R_{CI} - R_{nr})$$

$$\vec{\nabla} \cdot \vec{J}_p = q (G_{VC} + G_{VI} - R_{CV} - R_{IV} - R_{nr})$$

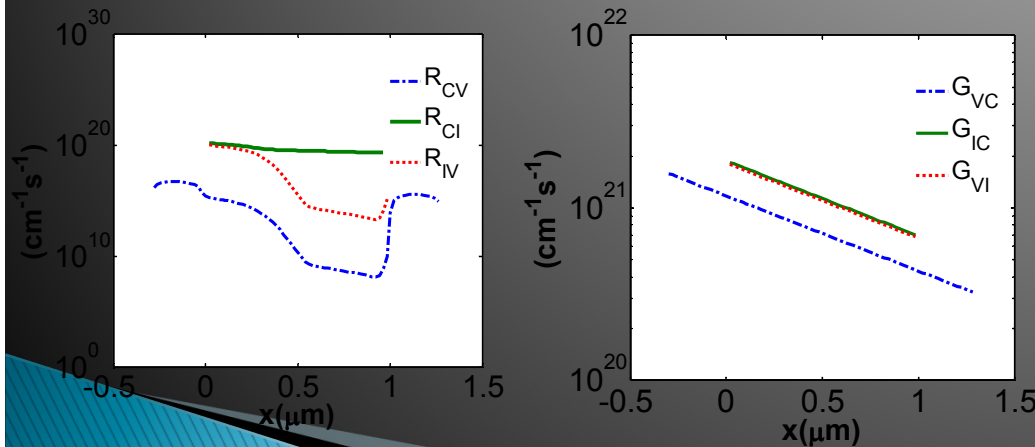
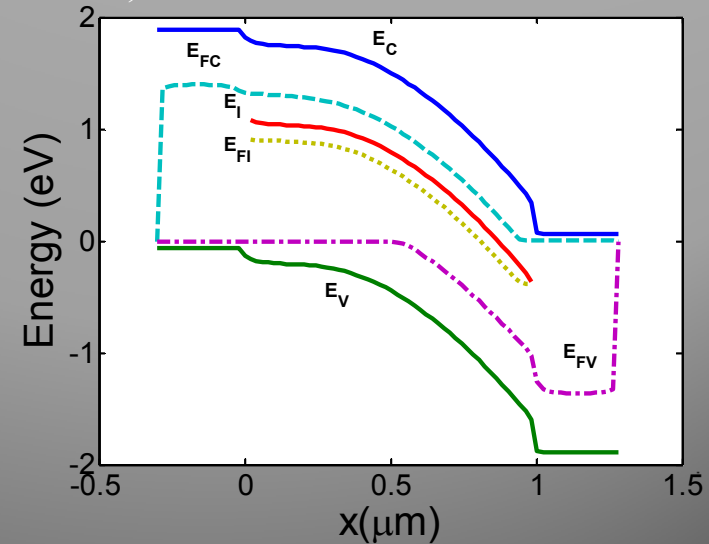
Where ψ is electrostatic potential, n and p are electron and hole concentration. f is the filling of the intermediate band. N_I is the IB density of states.

This cannot be simply incorporated into existing drift-diffusion model

Lightly Doped Case

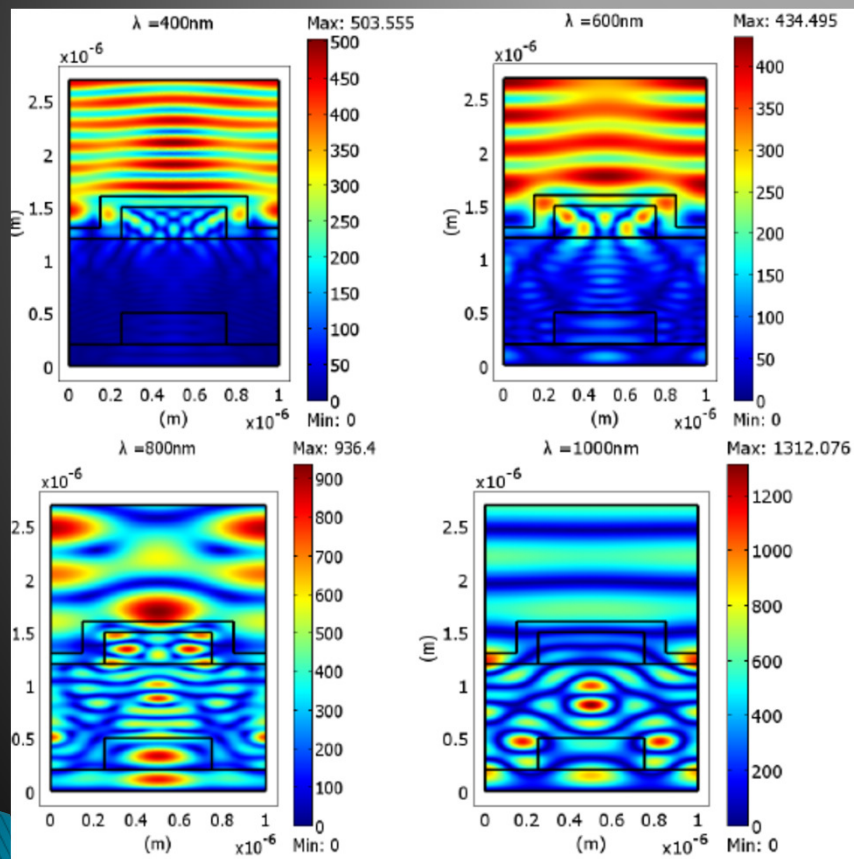
- E_{FI} is significantly below E_I , predicted high efficiency may not be achievable in practice unless
 - ✓ Asymmetric optical absorption cross section
 - ✓ efficient field emission or thermionic field emission exist between IB and CB.

$\alpha_{VC} = \alpha_{IC} = \alpha_{VI} = 10^4 \text{ cm}^{-1}$, $E_G = 1.95 \text{ eV}$, $E_I = 1.24 \text{ eV}$, $\mu_n = \mu_h = 100 \text{ cm}^2/\text{Vs}$, $W = 1 \text{ }\mu\text{m}$, $N_I = 10^{18} \text{ cm}^{-3}$ and N_A (p-emitter) = N_D (n-emitter) = 10^{18} cm^{-3}



- The band diagram deviate from conventional $p-i-n$ ($p-\pi-n, n p-v-n$) type picture, resulting from the charge in the intermediate band

Periodic Grating Structure



Helmholtz equation is solved for E-field

$$\nabla^2 E_z(\vec{r}) + \omega^2 \mu \epsilon E_z(\vec{r}) = 0$$

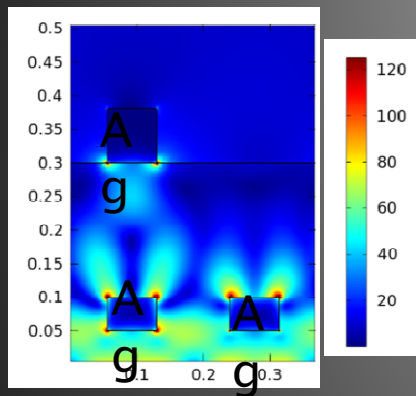
- For $\lambda = 400\text{ nm}$, the incoming wave decays rapidly in device
- For $\lambda = 1000\text{ nm}$, wave bounces back and forth

Electric field profile for cells with periodic grating couplers

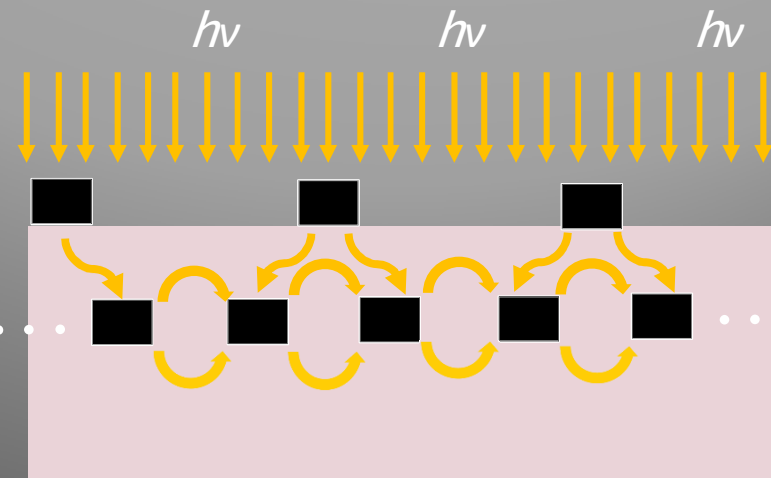
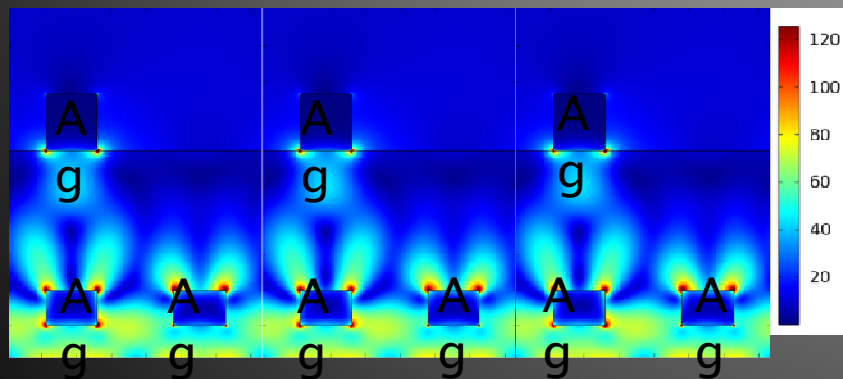
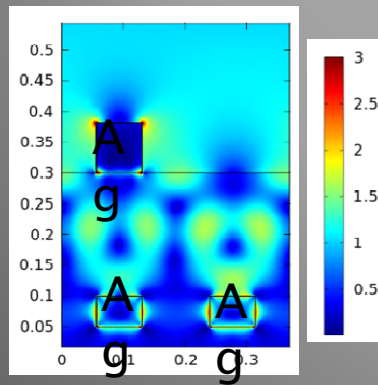
Surface Plasmon Photovoltaics

- ✓ Using Surface Plasmon to increase solar cell photonic property
- ✓ Waveguiding, slow light, slow Bloch mode, and energy transfer

Field Profile



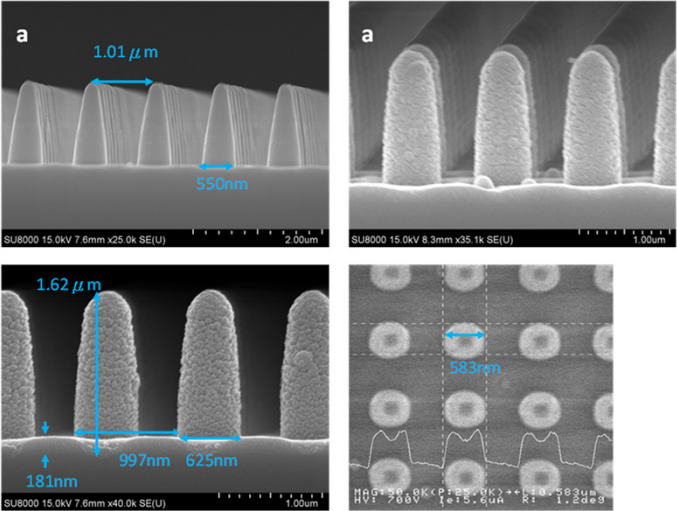
Eigen mode



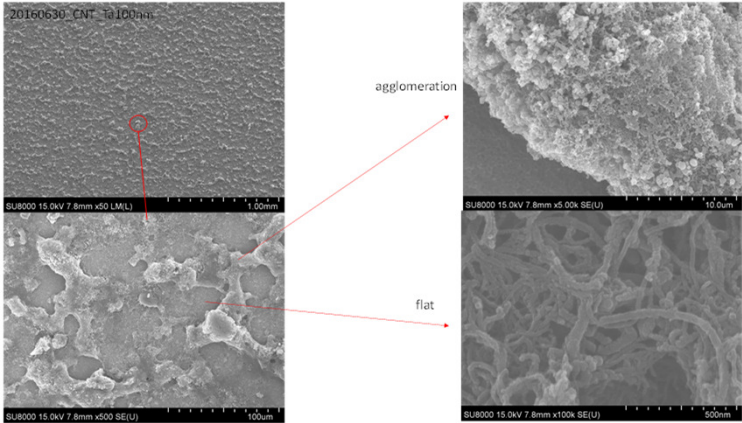
Device Processing

Silicon Processing

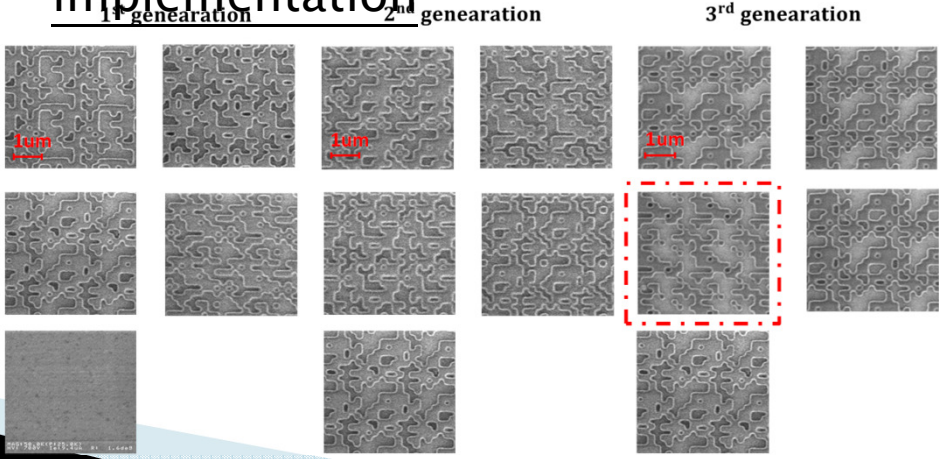
Paper figure (Taper structure 300-1000)



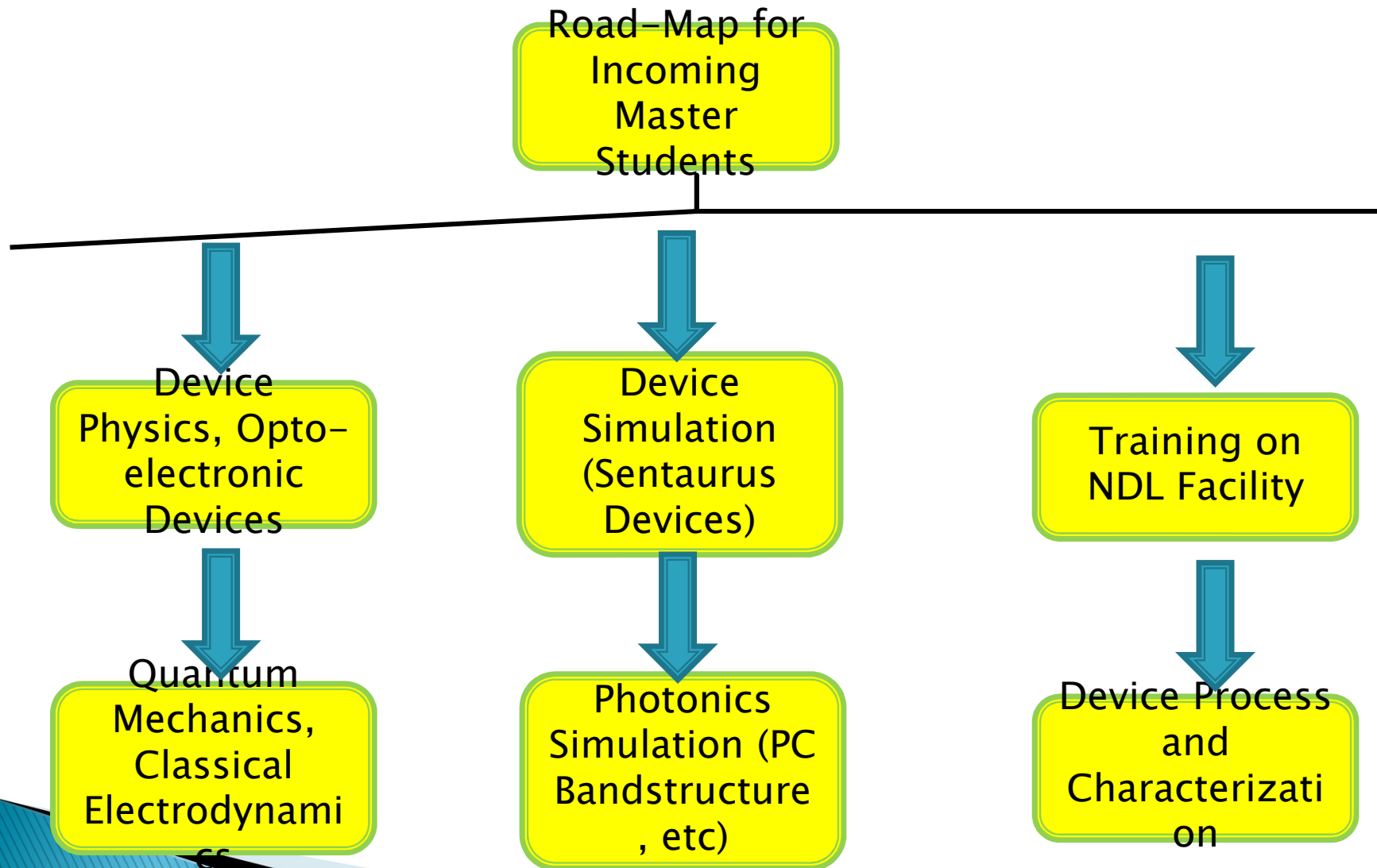
Material Processing



Advanced mask design and implementation



Theoretical and Process in parallel



Direct PhD, great theorist , TSMC



**Excellent
IIT exchange student**



**Graduate in 1 year, process integration
TSMC**



**Direct PhD , and my first PhD
student, Sze-Ming Fu**



Thank you, and Welcome your visit!

Office: ED503
Phone: 0921755140
Email: hdttd5746@gmail.com
Lab: ED314